Refined process category	Gas /										
	CF_4	C_2F_6	CHF_3	CH_2F_2	C_3F_8	$c\text{-}C_4F_8$	NF_3	SF_6	C_4F_6	C_5F_8	C_4F_8O
PATERNING/ETCHING											
Oxide etch											
1-U_i	0.2-0.8	0.2-0.7	0.2-0.7	0.02-0.3	N/A	0.1-0.3	0.1-0.4	0.1-0.4	0.05-0.5	0.05-0.3	N/A
PCF_4	N/A	0.05-0.5	0.01-0.8	0.05-0.1	N/A	0.01-0.3	N/A	N/A	0.02-0.4	0.02-0.4	N/A
PC_2F_6	N/A	N/A	N/A	N/A	N/A	0.01-0.3	N/A	N/A	0.02-0.3	0.02-0.3	N/A
PC_3F_8	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A
Nitride etch											
1-U_i	0.2-0.8	0.2-0.7	0.1-0.7	0.02-0.3	N/A	0.05-0.3	0.1-0.4	0.1-0.4	0.05-0.2	0.05-0.3	N/A
PCF_4	N/A	0.05-0.5	0.01-0.8	0.05-0.1	N/A	0.02-0.3	N/A	N/A	0.02-0.4	0.02-0.4	N/A
PC_2F_6	N/A	N/A	N/A	N/A	N/A	0.005-0.3	N/A	N/A	0.02-0.3	0.02-0.3	N/A
PC_3F_8	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A
Silicon etch											
1-U_i	0.2-0.8	0.2-0.7	0.2-0.7	0.02-0.3	N/A	0.1-0.3	0.1-0.4	0.1-0.4	0.05-0.2	0.05-0.3	N/A
PCF_4	N/A	0.05-0.5	0.01-0.8	0.05-0.1	N/A	0.01-0.3	N/A	N/A	0.02-0.4	0.02-0.4	N/A
PC_2F_6	N/A	N/A	N/A	N/A	N/A	0.01-0.3	N/A	N/A	0.02-0.3	0.02-0.3	N/A
PC_3F_8	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A
Metal etch											
1-U_i	0.2-0.8	0.2-0.7	0.2-0.7	0.02-0.3	N/A	0.1-0.3	0.1-0.4	0.1-0.4	0.05-0.2	0.05-0.3	N/A
PCF_4	N/A	0.05-0.5	0.01-0.8	0.05-0.1	N/A	0.01-0.3	N/A	N/A	0.02-0.4	0.02-0.4	N/A
PC_2F_6	N/A	N/A	N/A	N/A	N/A	0.01-0.3	N/A	N/A	0.02-0.3	0.02-0.3	N/A
PC_3F_8	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A
CHAMBER CLEANING											
In situ plasma cleaning											
1-U_i	0.8-0.95	0.4-0.8	N/A	N/A	0.2-0.6	005-0.3	0.05-0.2	N/A	N/A	0.05-0.2	0.05-0.2
PCF_4	N/A	0.05-0.2	N/A	N/A	0.05-0.2	0.05-0.2	0.05-0.1	N/A	N/A	0.05-0.2	0.05-0.2
PC_2F_6	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A
PC_3F_8	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	0.02-0.08
Remote plasma cleaning											
1-U_i	N/A	N/A	N/A	N/A	N/A	N/A	0.005-0.03	N/A	N/A	N/A	N/A
PCF_4	N/A	N/A	N/A	N/A	N/A	N/A	0.0001-0.2	N/A	N/A	N/A	N/A
PC_2F_6	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A
PC_3F_8	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A

Refined process category	Gas /										
	CF_4	C_2F_6	CHF_3	CH_2F_2	C_3F_8	$c\text{-}C_4F_8$	NF_3	SF_6	C_4F_6	C_5F_8	C_4F_8O
In situ thermal cleaning											
1-U_i	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A
PCF_4	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A
PC_2F_6	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A
PC_3F_8	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A
WAFER CLEANING											
Bevel cleaning											
1-U_i	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A
PCF_4	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A
PC_2F_6	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A
PC_3F_8	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A
Ashing											
1-U_i	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A
PCF_4	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A
PC_2F_6	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A
PC_3F_8	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A	N/A